

UNIFORM AIRFLOW DIFFUSER

ABSTRACT

The present invention is directed to a uniform airflow diffuser for utilization in a process chamber, such as a process chamber utilized in the manufacture of semiconductor chips. The uniform airflow diffuser is suitable for generating a back flow of air sufficient to cause the airflow to be distributed across the airflow diffuser. The resultant build-up in pressure in the plenum area may result in uniform airflow through a plurality of holes included in the airflow diffuser yielding substantially laminar airflow through the chamber.

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